

ABSTRACT

Disclosed are a wafer boat and a furnace tube apparatus. The wafer boat is used for carrying multiple layers of substrates spaced apart along a vertical direction in the furnace tube apparatus. The wafer boat comprises a plurality of heaters spaced apart along the vertical direction. The heaters are configured to heat the central regions of the substrates when the wafer boat carries the substrates. The wafer boat of the present invention can raise the temperature of the central regions of the substrates, so as to improve the uniformity of film thickness after film formation.